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Enhancement of photoinscription process in fused silica by thermal treatment (Withdrawal Notice)

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Badrinath Vadakkapattu C.,¹ Madhura R. Somayaji²

¹Karlsruhe School of Optics and Photonics (Germany)

²Lab. Hubert Curien, Univ. of Lyon, Univ. Jean Monnet (France)

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